

PO1057

**Infrared gas phase study on plasma-polymer interactions in high-current air-like dielectric barrier discharge**

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A high current diffuse dielectric barrier discharge (DBD) was operated in air-like gas mixture in an atmospheric-pressure roll-to-roll plasma reactor. The exhaust gas from the discharge was studied using a high-resolution Fourier-transform infrared (FTIR) spectrometer in the range from 750 to 3000  $\text{cm}^{-1}$ . The absorption features of  $\text{H}_x\text{N}_y\text{O}_z$ ,  $\text{CO}_x$ , and  $\text{HCOOH}$  (formic acid) were identified and used to establish production rates (X) for these stable products. The  $\text{H}_x\text{N}_y\text{O}_z$  chemistry was discussed according to the reaction pathways for plasma remediation and can be characterised by  $X(\text{HNO}_2) < X(\text{N}_2\text{O}) < X(\text{NO}_2) < X(\text{NO})$ . In this study it was observed that  $\text{HCOOH}$  can be a sensitive indicator for the etching of the polymer substrate in which the oxygen content plays a main role.  $\text{CO}_x$  is produced at high rates as soon as the polymer etching occurs while other  $\text{CO}_x$  sources (e.g. impurities) are at least 1 order less efficient in production. OH cannot be observed in the absorption spectra because of its high reactivity and therefore short lifetime. But the increase in the production of  $\text{HCOOH}$  and  $\text{HNO}_2$  when PEN etching occurs indicates that OH may be produced from the oxidation of PEN. The absence of  $\text{O}_3$  is attributed to the high electric field and high power density (therefore high temperature) in this study.

**Keywords**

FTIR

infrared

molecule production rate

atmospheric pressure

plasma measurements